**H2O on PuO**

**10/01/2013**

Old Si chip from last year still in the machine .

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 4, 1V/3.2A 34V/21mA 700V/ 1.2mA -- 7e-7

001 ov

002 Pu4f

003 O1s

004 F1s

005 HeII

sputter cleaning about Noon 2 h with 2kV at 5e-5mbar Ar in PK

006 ov

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

300s 3.7V/2.9A 41V/10mA 700V/ 1.6mA -- 1.1e-6

007 HeII rod position 0

008 HeII rod position 500

009 pu4f

010 ov

011 n1s

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

180s 3.9V/3.1A 41V/17mA 700V/ 1.9mA -- 4.4e-7

012 HeII RöRö was still on….

013 HeII

014 ov

**11/01/2012**

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 3.9V/3.1A 30/20mA 700V/ 1.4mA -- 7.9e-7 5e-7

015 HeII

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 4.0V/3.1A 30/25mA 700V/ 2.4mA -- 8.6e-7 1e-6

016 HeII

017 HeI

018 ov

019 pu4f

020 o1s

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 3.9V/3.1A 30/25mA 700V/ 1.7mA -- 8.0e-7 5e-6

021 HeII

022 HeI

023 pu4f

024 o1s

025 ov

**14/01/2013**

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 3.9V/3.1A 30/21mA 700V/ 1.7mA -- 8.8e-7 2e-6

026 HeII

027 HeI

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 4.0V/3.1A 30/29mA 700V/ 1.6mA -- 5.1e-7 7.5e-7

028 HeII

029 HeI

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

120s 3.6V/2.9A 30/13mA 650V/0.9mA -- 6.2e-7 5.0e-7

030 HeII

031 HeI

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

60s 3.4V/2.9A 30/12mA 650V/0.9mA -- 9.3e-7 0.00

032 HeII

033 HeI

034 pu4f

035 o1s

036 ov

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

60s 3.4V/2.9A 30/12mA 650V/1.3mA -- 1.23e-6 1e-6

037 HeII

038 HeI

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

60s 3.9V/3.1A 30/23mA 650V/0.7mA -- 2.3e-7 1e-6

040 HeII

041 HeI

**Dep[s] Fil. Work Pu(Targ.2) U(Targ.1) Ar O2**

60s 3.6V/3.0A 30/15mA 650V/0.6mA -- 3.0e -7 0.00

042 HeII

043 HeI

I'm always short cuts at the Pu target. Now start with uranium